

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	112	LEI-LAWRENCE-CHUNG-LAI LEI-LAWRENCE-CHUNG-IAI LEI-LAWRENCE-CHUNG LEI-LAWRENCE-CHANG-LAI LEI-LAWRENCE-C LEI-LAWRENCE YANG-SUSIE-XIURU	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/15 15:45
S2	1	YANG-SUSIE-XIURU	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/15 15:42
S3	1265	700/121.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/15 18:58
S4	112	LEI-LAWRENCE-CHUNG-LAI LEI-LAWRENCE-CHUNG-IAI LEI-LAWRENCE-CHUNG LEI-LAWRENCE-CHANG-LAI LEI-LAWRENCE-C LEI-LAWRENCE YANG-SUSIE-XIURU	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/15 15:45
S5	42	S4 and resistance	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/15 17:37
S6	14	("6291367" "5975994" "6113462" "6230069" "6268270" "6277014" "6465263" "6532555" "6535783" "6541401" "6546508" "6556881" "6652355" "6725402").PN.	US-PGPUB; USPAT	OR	ON	2005/06/15 17:48
S8	16	('6735492" "20020183986" "6381 564" "20030154062" "6529789" " 6774998" "6751518" "6678570"). PN.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/15 18:10
S9	807	700/121.ccls. and (metrology or measur\$5)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/15 18:59
S10	97	700/121.ccls. and ((metrology or measur\$5 or feedback or "feed back" or feed-back or "feed forward" or feed-forward) same ((CVD or deposit\$5) and (etch\$5 or trench\$5) and (planariz\$8 or polish\$6 or CMP)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/15 19:02

S11	22	700/121.ccls. and ((metrology or measur\$5 or feedback or "feed back" or feed-back or "feed forward" or feed-forward) same ((CVD or deposit\$5) and (etch\$5 or trench\$5) and (planariz\$8 or polish\$6 or CMP)) same (resistance or area or "cross section" or "cross-section"))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/16 14:54
S12	3	"6644382".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/16 14:47
S13	50	("4363816" "4781750" "4381301" "4520023" "4317823" "4410527" "5484949" "4543166" "4265816" "4538009" "4554387" "4575467" "4503073" "4550101" "5565491" "4830714" "4853440" "5372298" "5451577" "5559083" "5583242" "4309352" "4368066" "4385174" "4447619" "4585780" "4762827" "4797451" "4980458" "5234152" "5260291" "5316971" RE35948 "5840992" "5908944" "4267381" "4348322" "4367236" "4377576" "4405628" "4485240" "4496727" "4518535" "4519851" "4755557" "4912232" "5185356" "5287967" "5426102" "5435179").pn.	US-PGPUB; USPAT	OR	ON	2005/06/16 14:48
S14	733	(semiconductor or wafer) and ((metrology or measur\$5 or feedback or "feed back" or feed-back or "feed forward" or feed-forward) same ((CVD or deposit\$5) and (etch\$5 or trench\$5) and (planariz\$8 or polish\$6 or CMP)) same resistance)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/16 15:01
S15	271	(semiconductor or wafer) and ((metrology or measur\$5 or feedback or "feed back" or feed-back or "feed forward" or feed-forward) same ((CVD or deposit\$5) and (etch\$5 or trench\$5) and (planariz\$8 or polish\$6 or CMP)) same resistance same thickness)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/16 15:00
S16	4421	resistance near uniform\$5	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/16 15:00

S17	522	resistance adj uniformity	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/16 15:00
S18	31	(semiconductor or wafer) and ((metrology or measur\$5 or feedback or "feed back" or feed-back or "feed forward" or feed-forward) same ((CVD or deposit\$5) and (etch\$5 or trench\$5) and (planariz\$8 or polish\$6 or CMP))) and (resistance near uniform\$5)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/16 15:10
S19	266	(semiconductor or wafer) and ((planariz\$8 or polish\$6 or CMP) same (resistance near2 (line or cross-section or "cross section"))))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/16 15:12
S20	20	(semiconductor or wafer) and ((planariz\$8 or polish\$6 or CMP) same (resistance near2 (line or cross-section or "cross section")))) same (metrology or measur\$5 or feedback or "feed back" or feed-back or "feed forward" or feed-forward))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/16 15:43
S21	1	"line resistance uniformity"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/16 15:43
S22	5	("4793895" "5219787" "5234868" "6271047" "6326299").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2005/06/17 13:20
S23	0	trench\$5 with trapedoid\$5 with top with bottom	US-PGPUB; USPAT; USOCR	OR	ON	2005/06/17 13:21
S24	7	trench\$5 with trapezoid\$5 with top with bottom	US-PGPUB; USPAT; USOCR	OR	ON	2005/06/17 13:31
S25	3	(("top critical dimension" or "top CD") and ("bottom critical dimension" or "bottom CD")) same trench same (metrology or measur\$5)	US-PGPUB; USPAT; USOCR	OR	ON	2005/06/17 14:06
S26	267	trench\$5 with area with top with bottom	US-PGPUB; USPAT; USOCR	OR	ON	2005/06/17 13:31

S27	22	trench\$5 with area with top with bottom with (width or dimension)	US-PGPUB; USPAT; USOCR	OR	ON	2005/06/17 13:31
S28	2	(trench\$5 with area with top with bottom with (width or dimension)) same resistance	US-PGPUB; USPAT; USOCR	OR	ON	2005/06/17 13:32
S29	23	(trench\$5 with (resistance or area) with top with bottom with (width or dimension))	US-PGPUB; USPAT; USOCR	OR	ON	2005/06/17 13:38
S30	45	(trench\$5 with ((calculat\$5 or determin\$5) near area))	US-PGPUB; USPAT; USOCR	OR	ON	2005/06/17 13:50
S31	1	(trench\$5 with ((calculat\$5 or determin\$5) near area)) same (top and bottom)	US-PGPUB; USPAT; USOCR	OR	ON	2005/06/17 13:39
S32	2501	(trench\$5 near area)	US-PGPUB; USPAT; USOCR	OR	ON	2005/06/17 13:50
S33	33	(trench\$5 near area) with (top and bottom)	US-PGPUB; USPAT; USOCR	OR	ON	2005/06/17 13:54
S34	6	(""top critical dimension" or "top CD") and ("bottom critical dimension" or "bottom CD")) same trench same resistance	US-PGPUB; USPAT; USOCR	OR	ON	2005/06/17 13:56
S35	82	top same bottom same (width or dimension or CD) same trench same resistance	US-PGPUB; USPAT; USOCR	OR	ON	2005/06/17 14:02
S36	1	top same bottom same (width or dimension or CD) same trench same (line near resistance)	US-PGPUB; USPAT; USOCR	OR	ON	2005/06/17 14:02
S37	148	trench same (line near resistance)	US-PGPUB; USPAT; USOCR	OR	ON	2005/06/17 14:02
S38	53	trench same (line near resistance) same (width or dimension)	US-PGPUB; USPAT; USOCR	OR	ON	2005/06/17 14:03
S39	10	trench same (line near resistance) same (width or dimension) same (top or bottom)	US-PGPUB; USPAT; USOCR	OR	ON	2005/06/17 14:03
S40	1	trench same (line near resistance) same (width or dimension) same (top and bottom)	US-PGPUB; USPAT; USOCR	OR	ON	2005/06/17 14:03
S41	540	("critical dimension" or CD or width) near2 (top or bottom)) same trench	US-PGPUB; USPAT; USOCR	OR	ON	2005/06/17 14:07
S42	398	("critical dimension" or CD or width) near2 (top or bottom)) with trench	US-PGPUB; USPAT; USOCR	OR	ON	2005/06/17 14:07

S43	283	(("critical dimension" or CD or width) near (top or bottom)) with trench	US-PGPUB; USPAT; USOCR	OR	ON	2005/06/17 14:07
S44	38	(("critical dimension" or CD or width) near (top and bottom)) with trench	US-PGPUB; USPAT; USOCR	OR	ON	2005/06/17 14:40
S45	4784	trench near (width or "critical dimension" or CD)	US-PGPUB; USPAT; USOCR	OR	ON	2005/06/17 14:41
S46	4	(trench near (width or "critical dimension" or CD)) with (measur\$6 or metrology) with top with bottom	US-PGPUB; USPAT; USOCR	OR	ON	2005/06/17 14:46
S47	134	(trench near (width or "critical dimension" or CD)) with (measur\$6 or metrology)	US-PGPUB; USPAT; USOCR	OR	ON	2005/06/17 14:47
S48	11	((trench near (width or "critical dimension" or CD)) with (measur\$6 or metrology)) same resistance	US-PGPUB; USPAT; USOCR	OR	ON	2005/06/17 14:49
S50	26	((trench or line) near (width or "critical dimension" or CD)) with (measur\$6 or metrology) with top with bottom	US-PGPUB; USPAT; USOCR	OR	ON	2005/06/17 19:06
S51	571	resistance with four with point with probe	US-PGPUB; USPAT; USOCR	OR	ON	2005/06/17 19:07
S52	1	resistance with four with point with probe with trench	US-PGPUB; USPAT; USOCR	OR	ON	2005/06/17 19:07
S53	20	(resistance with four with point with probe) with (trench\$5 or line)	US-PGPUB; USPAT; USOCR	OR	ON	2005/06/17 19:26
S54	2	(resistance with four with point with probe) same (trench\$5)	US-PGPUB; USPAT; USOCR	OR	ON	2005/06/17 19:26
S55	978	700/108-110.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/17 21:12
S56	77	700/108-110.ccls. and resistance and (wafer or semiconductor)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/17 21:12

S57	25	700/108-110.ccls. and resistance and (wafer or semiconductor) and (polish\$5 or planariz\$5 or CMP)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/17 21:13
S58	88	700/108-110.ccls. and (wafer or semiconductor) and (polish\$5 or planariz\$5 or CMP)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/17 21:13
S59	6392	438/14,17,626,631.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/17 21:14
S60	1582	438/14,17,626,631.ccls. and resistance	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/17 21:14
S61	729	438/14,17,626,631.ccls. and resistance and (polish\$5 or planariz\$5 or CMP)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/17 21:15
S62	697	438/14,17,626,631.ccls. and resistance and (polish\$5 or planariz\$5 or CMP) and (trench or etch\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/17 21:15
S63	655	438/14,17,626,631.ccls. and resistance and (polish\$5 or planariz\$5 or CMP) and (trench or etch\$4) and deposit\$6	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/17 21:15